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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/082,019	02/20/2002	Young-Joo Cho	2522-14	1906

7590 09/29/2003

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EXAMINER

DANG, PHUC T

ART UNIT	PAPER NUMBER
2818	

DATE MAILED: 09/29/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/082,019	CHO ET AL.	
	Examiner	Art Unit	
	PHUC T DANG	2818	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM
 THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 20 February 2002.

2a) This action is **FINAL**. 2b) This action is non-final.

3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 1-36 is/are pending in the application.

4a) Of the above claim(s) _____ is/are withdrawn from consideration.

5) Claim(s) _____ is/are allowed.

6) Claim(s) 1-36 is/are rejected.

7) Claim(s) _____ is/are objected to.

8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.

10) The drawing(s) filed on 20 February 2002 is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).

11) The proposed drawing correction filed on _____ is: a) approved b) disapproved by the Examiner.
 If approved, corrected drawings are required in reply to this Office action.

12) The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).

a) All b) Some * c) None of:

1. Certified copies of the priority documents have been received.

2. Certified copies of the priority documents have been received in Application No. _____.

3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).
 a) The translation of the foreign language provisional application has been received.

15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

1) Notice of References Cited (PTO-892)

2) Notice of Draftsperson's Patent Drawing Review (PTO-948)

3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____.

4) Interview Summary (PTO-413) Paper No(s). _____.

5) Notice of Informal Patent Application (PTO-152)

6) Other: _____.

Art Unit: 2818

DETAILED ACTION

Oath/Declaration

1. The oath/declaration filed on February 20, 2002 is acceptable.

Priority

2. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Specification

3. The specification has been checked to the extent necessary to determine the presence of all possible minor errors. However, the applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Objections

4. Claim 20 is objected to because of the informalities as follows:

In claim 20, line 10, the term "dependant" should change to – dependent --.

Claim Rejections - 35 USC § 102

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was

Art Unit: 2818

made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(f) or (g) prior art under 35 U.S.C. 103(a).

5. Claims 1-19 are rejected under 35 U.S.C. 102 (e) as being anticipated by Goo et al. (U.S. Patent No. 6,489,252 B2).

Goo et al. discloses a method of forming an interlayer, the method comprising:
preparing a substrate (51, Fig. 3) with a wiring patterns (53, Fig. 3);
forming an insulating film (55, Fig. 4) on the substrate;
chemical mechanical polishing the insulating film and exposing an upper portion of the wiring pattern;
coating the polished insulation and exposed portion of the wiring pattern with spin on glass composition to form a film;
pre-baking the film in a temperature range of 50 to 350°C;
after the pre-baking, hard-baking the film in a temperature range of 300 to 350°C; and
heat-treating the film in an oxidation atmosphere [col. 5, lines 16-col. 7, lines 15].

6. Claims 20-21 are rejected under 35 U.S.C. 102 (e) as being anticipated by Goo et al. (U.S. Patent No. 6,489,252 B2).

Goo et al. discloses a method of forming an interlayer, the method comprising:
forming insulating material (53, Fig. 3) on a semiconductor substrate (51, Fig. 3);
polishing the insulating material using a chemical mechanical polishing process and
exposing an upper portion of a conductive pattern (55, Fig. 4) of the semiconductor substrate;

Art Unit: 2818

coating the polished insulating material and the upper portion of the conductive pattern with a spin on glass composition and forming a film, the coating using polysilazane in the spin on glass composition;

pre-baking the film at a temperature below 500°C;

determining if a thickness of the film exceeds a crack free thickness limit;

decreasing a thickness of the film dependent on the determining; and

heat-treating the film in an oxidation atmosphere [col. 5, lines 16-col. Col. 7, lines 15].

7. Claims 22-36 are rejected under 35 U.S.C. 102 (e) as being anticipated by Goo et al. (U.S. Patent No. 6,489,252 B2).

Goo et al. discloses a method of forming an interlayer dielectric film, the method comprising:

coating a spin on glass composition on a semiconductor substrate that has been formed with a conductive pattern step, the coating using a polysilazane in the spin on glass composition;

curing the spin on glass composition to form a film;

outgassing the film, the outgassing comprises releasing silane gas; and

annealing and oxidizing the film [col. 5, lines 16-col. Col. 7, lines 15].

Conclusion

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Phuc T. Dang whose telephone number is 703-305-1080. The examiner can normally be reached on 8:00 am-5:00 pm.

Art Unit: 2818

9. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on 703-308-4910. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9306 for regular communications and 703-872-9306 for After Final communications.

10. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Phuc T. Dang

PD

Examiner

Dang Phuc

Art Unit 2818

August 29, 2003